

IN THE CLAIMS

1. (currently amended) A chemical vapor deposition process for depositing a coating comprising tungsten oxide on the surface of a glass substrate to produce a solar control glass which transmits a high percentage of incident light, ~~by~~ comprising directing a gaseous stream comprising tungsten oxyhalide or tungsten chloride and a source of oxygen on to the surface of the glass substrate, wherein the glass substrate is in the form of a hot glass ribbon, which is at a temperature in the range 500°C to 720°C during a float glass production process.

2. (original) A process according to claim 1 wherein the coating comprising tungsten oxide comprises a layer of tungsten oxide.

3. (previously presented) A process according to claim 1 wherein tungsten oxyhalide comprises a tungsten oxychloride.

4. (previously presented) A process according to claim 1 wherein tungsten oxyhalide or tungsten chloride comprises a substituted tungsten oxyhalide or tungsten chloride.

5. (previously presented) A process according to claim 1 wherein the source of oxygen comprises an ester.

6. (original) A process according to claim 5 wherein the ester has from 3 to 6 carbon atoms.

7. (previously presented) A process according to claim 5 wherein the ester is ethyl acetate or butyl acetate.

8. (previously presented) A process according to claim 1 wherein the gaseous stream contains oxygen gas.

9. (previously presented) A process according to claim 1 wherein the ratio of tungsten oxyhalide or tungsten chloride and the source of oxygen are such that the layer of tungsten oxide is deposited as non-stoichiometric tungsten oxide.

10. (previously presented) A process according to claim 1 wherein the gaseous stream contains a source of fluorine.

11. (original) A process according to claim 10 wherein the source of fluorine comprises hexafluoroethane, trifluoroacetic acid or hexafluoropropylene oxide.

12. (previously presented) A process according to claim 1 wherein tungsten oxyhalide or tungsten chloride is entrained in the gaseous stream by flowing inert gas over hot tungsten oxyhalide or tungsten chloride.

13. (original) A process according to claim 12 wherein tungsten oxyhalide or tungsten chloride is at a temperature in the range 170°C to 210°C.

14. (previously presented) A process according to claim 12 wherein the inert gas comprises nitrogen.

15. (previously presented) A process according to claim 1 wherein the source of oxygen comprises an ester and is entrained in the gaseous stream by contacting said ester with a flowing inert gas.

16. (original) A process according to claim 15 wherein the ester is at a temperature in the range 30°C to 45°C.
17. (previously presented) A process according to claim 1 wherein the tungsten oxide layer has a thickness in the range 70 to 180 nm.
18. (previously presented) A process according to claim 1 wherein the tungsten oxide layer is deposited at a growth rate in the range 3 to 25 nm s⁻¹.
19. (previously presented) A process according to claim 1 wherein the tungsten oxide layer is overcoated with a further layer.
20. (currently amended) A chemical vapor deposition process for coating glass in a float glass production process comprising directing a gaseous stream containing a tungsten compound and a source of oxygen on to the surface of a glass substrate thereby forming a non-stoichiometric tungsten oxide layer wherein the tungsten oxide layer is overcoated with a further layer.
21. (previously presented) A process according to claim 20 wherein the further layer comprises a metal oxide.
22. (previously presented) A process according to claim 20 wherein the further layer comprises fluorine doped tin oxide.
- 23-33 (canceled)
34. (previously presented) A process according to claim 1 wherein the glass substrate is at a temperature in the range 565°C to 655°C.

35. (previously presented) A process according to claim 1 wherein the tungsten oxide layer is deposited on to coated glass.

36. (previously presented) A process according to claim 35 wherein the coated glass has a coating comprising silicon oxide.

37. (previously presented) A process according to claim 36 wherein the coating comprising silicon oxide further contains carbon.

38. (currently amended) A chemical vapor deposition process for coating glass in a float glass production process comprising entraining a tungsten compound in a gas by flowing the gas over a tungsten compound at a temperature below its melting point and directing the gaseous stream on to the surface of a glass substrate thereby forming a tungsten oxide layer, wherein the glass substrate is at a temperature in the range of 500°C to 720°C.

39. (previously presented) A process according to claim 38 wherein the tungsten compound is tungsten halide, tungsten oxyhalide or tungsten carbonyl.

40. (currently amended) A method of coating glass in a chemical vapor deposition, float glass production process comprising

- (a) providing a glass substrate having a temperature in the range of 500°C to 720°C,
- (b) preparing a gaseous stream comprising a source of oxygen and a tungsten compound selected from the group consisting essentially of tungsten oxyhalide and tungsten chloride, and
- (c) directing the gaseous stream on to the glass substrate, thereby depositing a coating comprising tungsten oxide on the glass substrate.

41. (currently amended) A process for depositing a coating comprising tungsten oxide on the surface of a glass substrate in a chemical vapor deposition, float glass production process, by directing a gaseous stream comprising tungsten oxyhalide or tungsten chloride and an ester on to the surface of the glass substrate.

42. (previously presented) A coated glass produced by a process according to claim 1.

43. (previously presented) A multiple glazing unit comprising a coated glass according to claim 42 in spaced opposed relation to a glazing pane.

44. (previously presented) A process according to claim 1 wherein the tungsten oxyhalide comprises tungsten oxytetrachloride.